The NEXT GENERATION of EPITAXY



ALD System Conversions to Hollow Cathode Operation



- Conversion of Ultratech, Inc. Fiji® and Savannah® ALD systems
- · Oxides, nitrides, other
- Low oxygen contamination (no dielectrics)
- Low cost
- Scalable to large areas (more holes = greater area)
- High electron density similar to inductively coupled and microwave plasma sources
- Wide range of operating pressures (eg. from <100 mTorr to >100 Torr).
- Improved growth per cycle for many material systems

Related Papers:

- K. S. A. Butcher, B. W. Kemp, I. B. Hristov, P. Terziyska, P. W. Binsted and D. Alexandrov, Japanese Journal of Applied Physics **51** (2012) 01AF02.
- C. Ozgit-Akgun, E. Goldenberg, A. Kemal Okyay and N. Biyikili, Journal of Materials Chemisty C 2
 (2014) 2123.

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